

Docket No. 195425US77
 IN RE APPLICATION OF: Jianming Wang
 SERIAL NO: 09/654,078
 FILED: September 1, 2000
 FOR: DUAL DAMASCENE STRUCTURE AND METHOD OF MAKING



DAC

ASSISTANT COMMISSIONER FOR PATENTS
 WASHINGTON, D.C. 20231

SIR:

Transmitted herewith is an amendment in the above-identified application.

- No additional fee is required
- Small entity status of this application under 37 C.F.R. §1.9 and §1.27 is claimed.
- Additional documents filed herewith: Petition for Revival of an Application for Patent Abandoned Unintentionally Under 37 C.F.R. §1.137(b)
 Copy of Date-stamped Filing Receipt for May 29, 2002
 Amendment w/Marked-up Copy (10 pp.)

The Fee has been calculated as shown below:

CLAIMS	CLAIMS REMAINING		HIGHEST NUMBER PREVIOUSLY PAID	NO. EXTRA CLAIMS	RATE	CALCULATIONS
TOTAL	12	MINUS	20	0	× \$18 =	\$0.00
INDEPENDENT	1	MINUS	3	0	× \$84 =	\$0.00
		<input type="checkbox"/> MULTIPLE DEPENDENT CLAIMS		+ \$280 =		\$0.00
						TOTAL OF ABOVE CALCULATIONS
		<input type="checkbox"/> Reduction by 50% for filing by Small Entity				\$0.00
		<input type="checkbox"/> Recordation of Assignment		+ \$40 =		\$0.00
						TOTAL
						\$0.00

- A check in the amount of \$1,280.00 is attached.
- Please charge any additional Fees for the papers being filed herewith and for which no check is enclosed herewith, or credit any overpayment to deposit Account No. 15-0030. A duplicate copy of this sheet is enclosed.
- If these papers are not considered timely filed by the Patent and Trademark Office, then a petition is hereby made under 37 C.F.R. §1.136, and any additional fees required under 37 C.F.R. §1.136 for any necessary extension of time may be charged to Deposit Account No. 15-0030. A duplicate copy of this sheet is enclosed.

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AUG 07 2002

OFFICE OF PETITIONS

195425US



IN THE UNITED STATES PATENT & TRADEMARK OFFICE

#11

IN RE APPLICATION OF:

JIANMIN QIAO : GROUP ART UNIT: 2814

SERIAL NO: 09/654,078 :

FILED: SEPTEMBER 1, 2000 : EXAMINER: PHAM, H.

FOR: DUAL DAMASCENE STRUCTURE
AND METHOD OF MAKING

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AMENDMENT

AUG 07 2002

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

OFFICE OF PETITIONS

SIR:

In response to the Office Action dated November 29, 2001, please amend the application identified above as follows (marked-up copy of amendments attached):

IN THE SPECIFICATION

Please amend the specification as follows:

Amend the paragraph at page 5, lines 2-8, as follows:

(Amended) A dual damascene interconnect structure according to the invention includes a contact dielectric layer, an etch stop layer of undoped or doped silicon oxide on the contact dielectric layer, a trench layer on the etch stop layer, and a continuous electrically conductive interconnect passing through holes in the contact dielectric layer, the etch stop layer and the trench layer. The term "undoped" as used herein refers to a dopant concentration of less than 1.0 wt.%. Conversely, the term "doped" as used herein refers to a dopant concentration of greater than or equal to 1.0 wt.%.